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## Supplementary Information

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**Rationally integrated nickel sulfides for lithium storage: S/N co-**

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**doped carbon encapsulated NiS/Cu<sub>2</sub>S with greatly enhanced kinetic**

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**property and structural stability**

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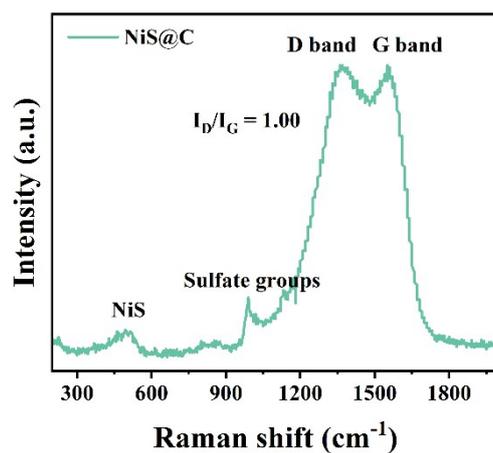
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Fig. S1 The Raman spectrum of NiS@C.

3 The Raman spectrum of NiS@C shows similar results with NiS/Cu<sub>2</sub>S@N/S-C. It is

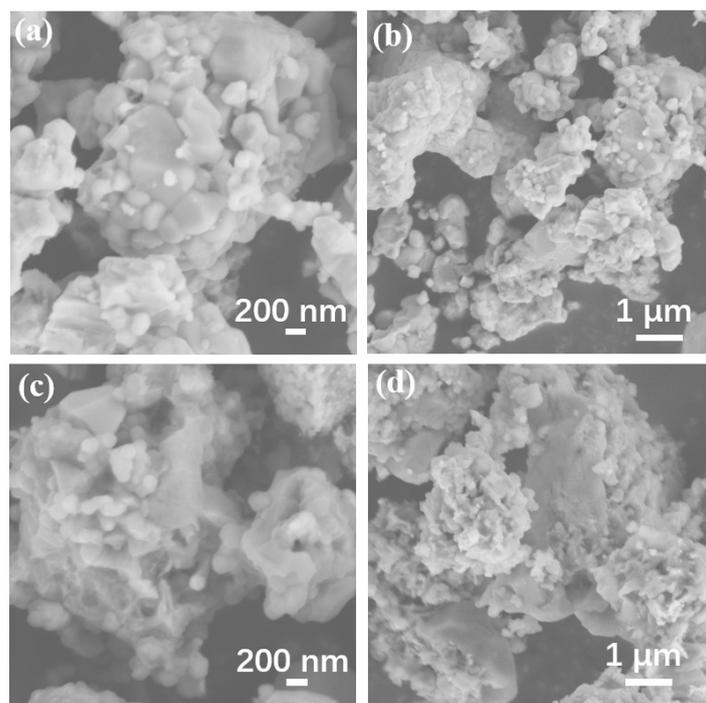
4 worth mentioning that the additional peak at 990 cm<sup>-1</sup> in the Raman spectrum of NiS@C

5 corresponds to the characteristic peak of sulfate groups<sup>1, 2</sup>, which is ascribed to the

6 inevitable surface sulfur oxidation of NiS@C.

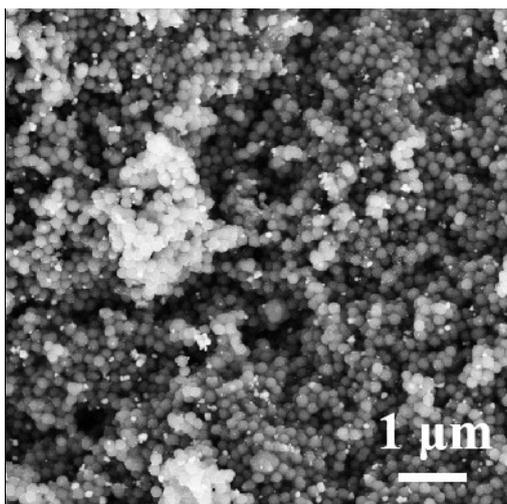
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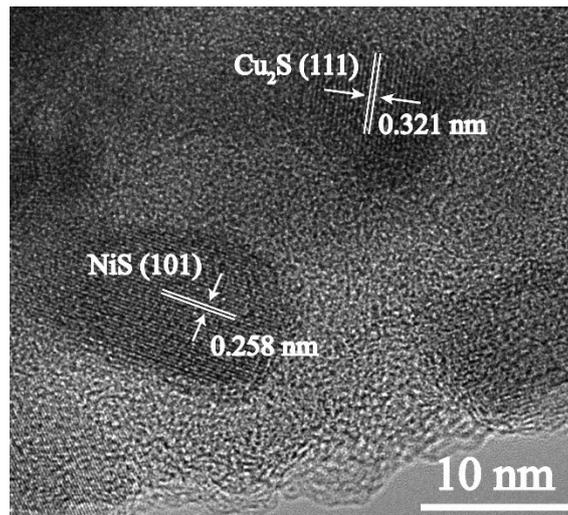
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**Fig. S2** SEM images of (a)-(b)Pure-NiS and (c)-(d) NiS@C.



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**Fig. S3** SEM low magnification image of NiS/Cu<sub>2</sub>S@N/S-C.



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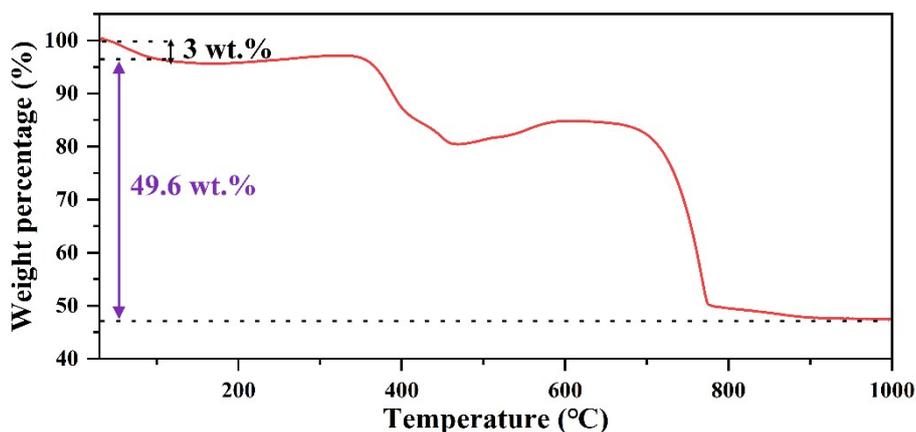
**Fig. S4** HRTEM image of NiS/Cu<sub>2</sub>S@N/S-C.

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**Table S1.** The results of ICP-OES for the NiS/Cu<sub>2</sub>S@N/S-C

Elements	concentration (mg/L)
Ni	9.1468
Cu	2.4830

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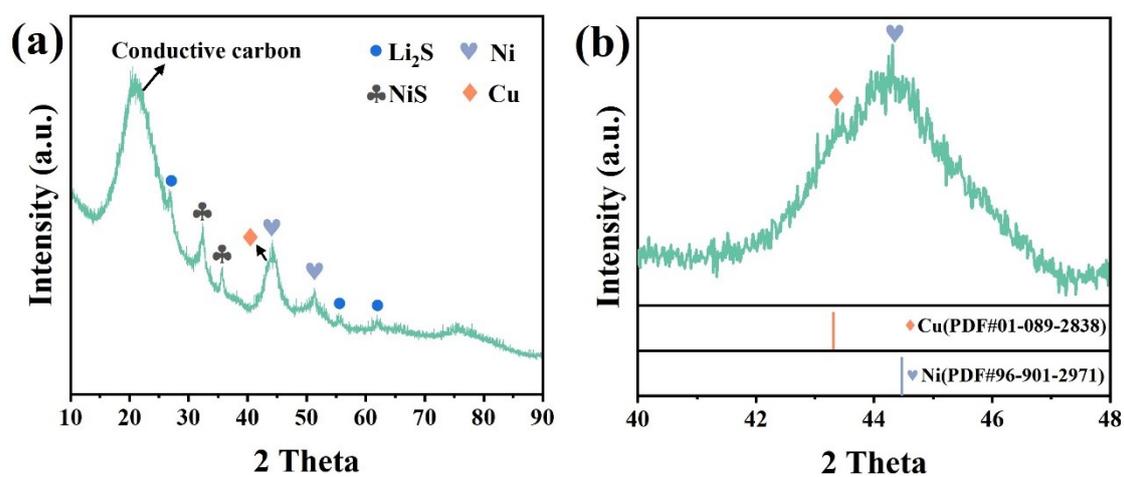
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**Fig. S5** TGA curve of the NiS/Cu<sub>2</sub>S@N/S-C

5 Firstly, ICP-OER was performed to confirm the content of NiS and Cu<sub>2</sub>S. According to  
6 the results of ICP-OES (Table S1), the mass ratio of Ni and Cu in the NiS/Cu<sub>2</sub>S@N/S-C  
7 is 3.68:1, suggesting the mass ratio of NiS and Cu<sub>2</sub>S is 4.54:1. Meanwhile, the atomic  
8 ratio of Ni and Cu can be calculated to 4:1, indicating the molar ratio of NiS and Cu<sub>2</sub>S  
9 is 8:1. Furthermore, the TGA test was conducted to was obtained to calculate the  
10 content of carbon under air atmosphere from 30 to 1000°C with a heating rate of  
11 10°C/min. As shown in Fig. S5, the mass loss below 100°C (3 wt.%) is ascribed to the  
12 loss of adsorption species (*e.g.* adsorption water) on the surface of the NiS/Cu<sub>2</sub>S@N/S-  
13 C. The following heating process involved combustion of carbon and redox reaction of  
14 metal sulfides with oxygen, that is, the process from NiS/Cu<sub>2</sub>S@N/S-C to NiO/CuO,  
15 SO<sub>2</sub> and combustion product of N/S-C. Accordingly, the overall mass loss (49.6 wt.%)  
16 can be equivalent to the mass of sulfur in NiS/Cu<sub>2</sub>S and the mass of N/S-C minus the  
17 mass of oxygen in the final metal oxides. Hence, the weight percentage of NiO/CuO  
18 was calculated as 47.4 wt.% ((100 - 3 - 49.6) wt.%), further suggesting the weight  
19 percentage of NiS and Cu<sub>2</sub>S are 45.4 and 9.9 wt.% based on the molar ratio of Ni/Cu  
20 and the difference of relative molecular mass between NiO/CuO and NiS/Cu<sub>2</sub>S.

1 Furthermore, the weight percentage of N/S-C can be equivalent to 100 wt.% minus the  
2 sum of the weight percentage of adsorption species (3 wt.%) and the weight percentage  
3 of NiS/Cu<sub>2</sub>S ((45.4 + 9.9) wt.%), that is 41.7 wt.%. Thus, the actual weight percentages  
4 of the Cu<sub>2</sub>S, NiS and N/S-C in the NiS/Cu<sub>2</sub>S@N/S-C hybrids can be normalized to 9.9,  
5 45.4 and 41.7 wt.%, respectively.  
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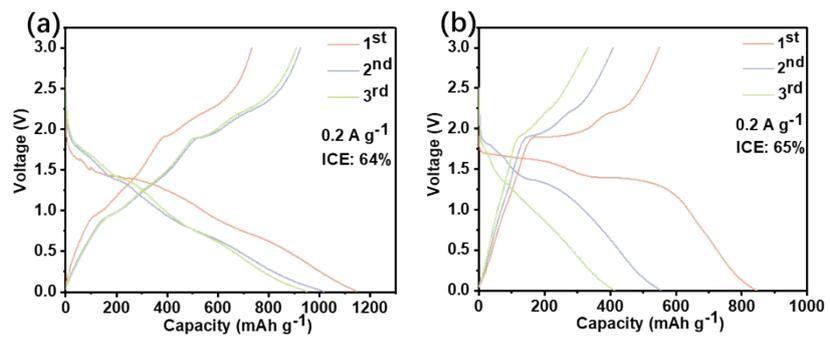


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3 **Fig. S6** (a) The XRD pattern of  $\text{NiS}/\text{Cu}_2\text{S}@N/\text{S}-\text{C}$  after discharge; (b) Partial enlargement curve  
4 in (a).

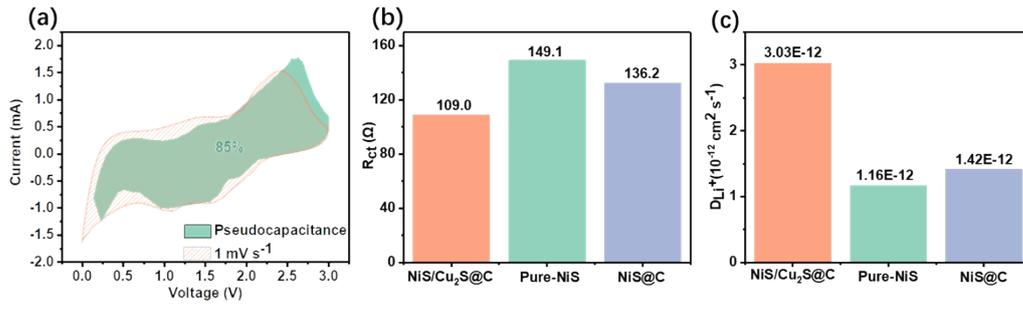
5 The anode materials were scraped from the collector (copper foil) for the *ex-situ* XRD  
6 test after discharge.

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**Fig. S7** Charge-discharge profiles of NiS@C and Pure-NiS at 0.2 A g<sup>-1</sup>.



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2 **Fig. S8** (a) contribution rate of pseudo-capacitance of NiS/Cu<sub>2</sub>S@N/S-C at 1 mV s<sup>-1</sup>, (b)-(c) the

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values of R<sub>ct</sub> and D<sub>Li<sup>+</sup></sub> of NiS/Cu<sub>2</sub>S@N/S-C, NiS@C and Pure-NiS.

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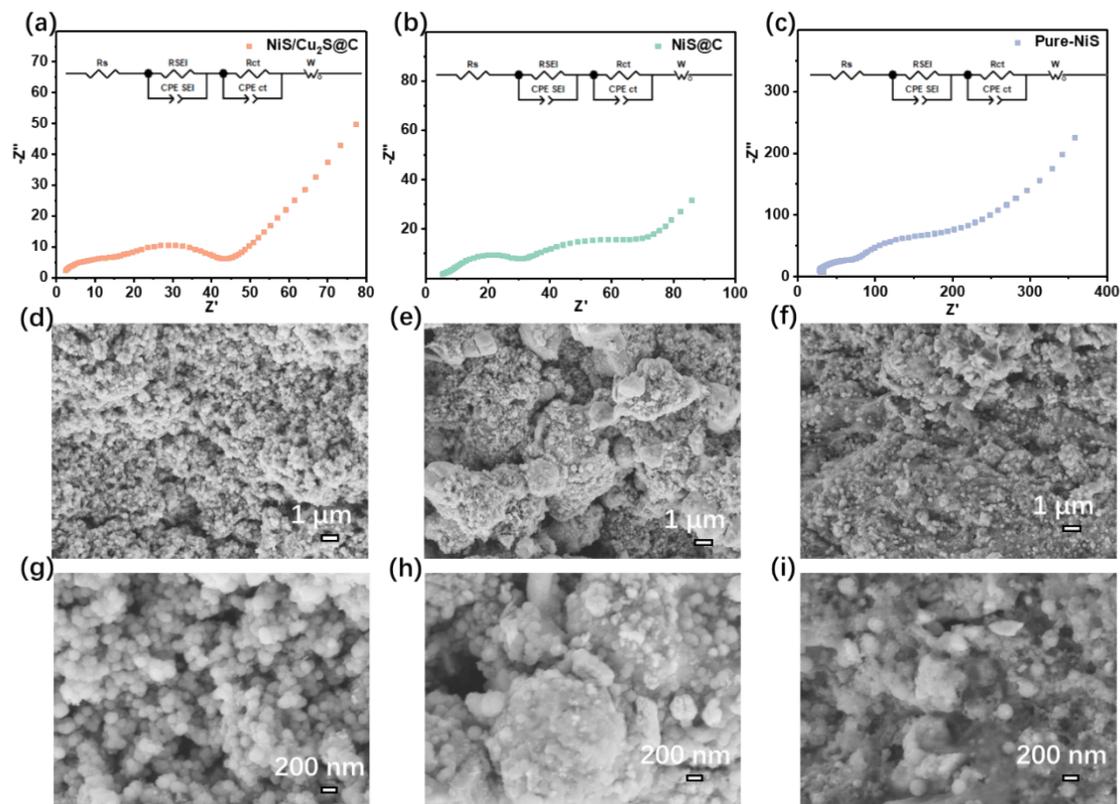
1 ***The calculation of the lithium-ion diffusion coefficients***

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$$Z_{re} = \sigma_w \omega^{-0.5} + R_s + R_{ct} \quad (S1)$$

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$$D_{Li^+} = 0.5 \frac{RT}{(A_{ac} F^2 \sigma_w C_{Li})^2} \quad (S2)$$

4       Where  $Z_{re}$ ,  $\omega$ ,  $R$ ,  $T$ , and  $C_{Li}$  are the real impedance in the low-frequency region,  
5 the angular frequency obtained from the low-frequency regime, the gas constant, the  
6 absolute temperature and the initial  $Li^+$  molar concentration in the electrolyte (1 mol  
7  $L^{-1}$ ), respectively.

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2 **Fig. S9** (a)-(c) Nyquist plots of NiS/Cu<sub>2</sub>S@S/N-C, NiS@C and Pure-NiS, SEM images of  
 3 NiS/Cu<sub>2</sub>S@ S/N-C, NiS@C and Pure-NiS at 1 A g<sup>-1</sup> after 100 cycles at (d)-(f) low magnification  
 4 and (g)-(i) high magnification, respectively.

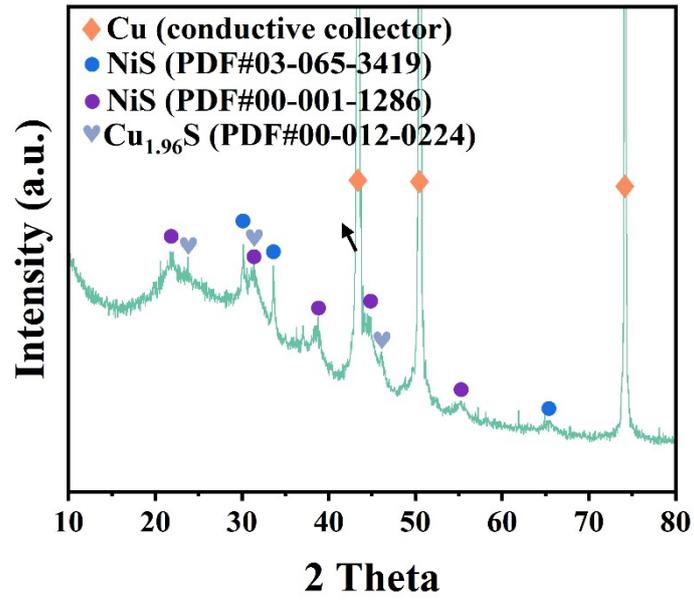
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1 **Table S2.** The resistance **results** of the NiS/Cu<sub>2</sub>S@N/S-C, NiS@C and Pure-NiS after 100th  
2 **cycles** at 1 A g<sup>-1</sup>

	NiS/Cu <sub>2</sub> S@N/S-C	NiS@C	Pure-NiS
R <sub>SEI</sub> (Ω)	43.7	85.5	294.5
R <sub>ct</sub> (Ω)	23.1	34.4	86.0

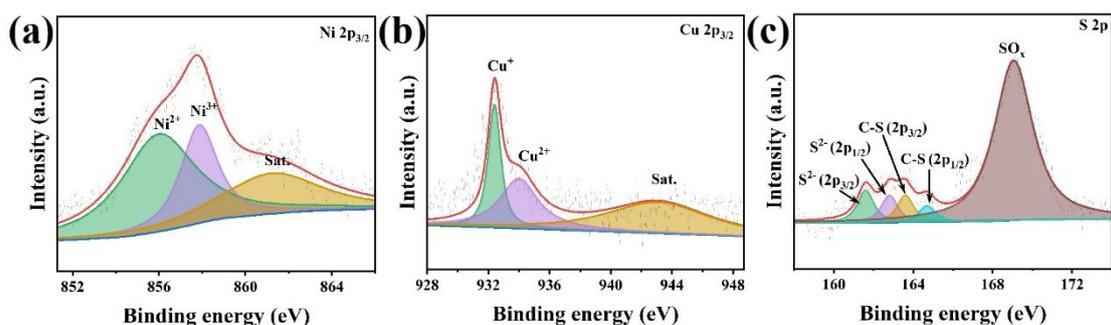
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**Fig. S10** The *ex-situ* XRD pattern of the NiS/Cu<sub>2</sub>S@N/S-C after 350 cycles at 1 A g<sup>-1</sup>. The characteristic peaks of NiS and Cu<sub>1.96</sub>S can still be clearly observed, which is consistent with the lithium storage mechanism mentioned in manuscript.



**Fig. S11** The high-resolution XPS spectra in the regions of Ni 2p (a), Cu 2p (b), S 2p (c) for the NiS/Cu<sub>2</sub>S@N/S-C after 350 cycles at 1 A g<sup>-1</sup>

The existence of Ni<sup>2+</sup> and Ni<sup>3+</sup> can also be confirmed according to the spectrum of Ni 2p<sub>3/2</sub> (Fig. S11a), which is similar to the pristine NiS/Cu<sub>2</sub>S@N/S-C, suggesting the retention of NiS<sup>3</sup>. The high-resolution spectrum of Cu 2p<sub>3/2</sub> (Fig. S11b) shows two obvious peaks at 932.4 and 934.0 eV, corresponding to the Cu<sup>+</sup> and Cu<sup>2+</sup>, respectively<sup>4</sup>, which is also similar to the pristine NiS/Cu<sub>2</sub>S@N/S-C. As illustrated in Fig. S11c, the peaks of S 2p<sub>3/2</sub> and 2p<sub>1/2</sub> of S<sup>2-</sup> (161.6 and 162.8 eV) further demonstrate the existence of NiS after long-term cyclings. The other two peaks at 163.8 and 165.1 eV can be attributed to the C-S bonding, demonstrating the retention of S-doped carbon matrix. In addition, the peak at 168.8 eV corresponds to the SO<sub>x</sub>, which may be ascribed to the further surface oxidation in the air after the electrode taken apart from the tested coin cell<sup>5</sup>.

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